

Supporting Information

Synthesis, Characterization, Thermal Properties of Silicon(IV) Compounds Containing Guanidinato Ligands and Their Potential as CVD Precursors

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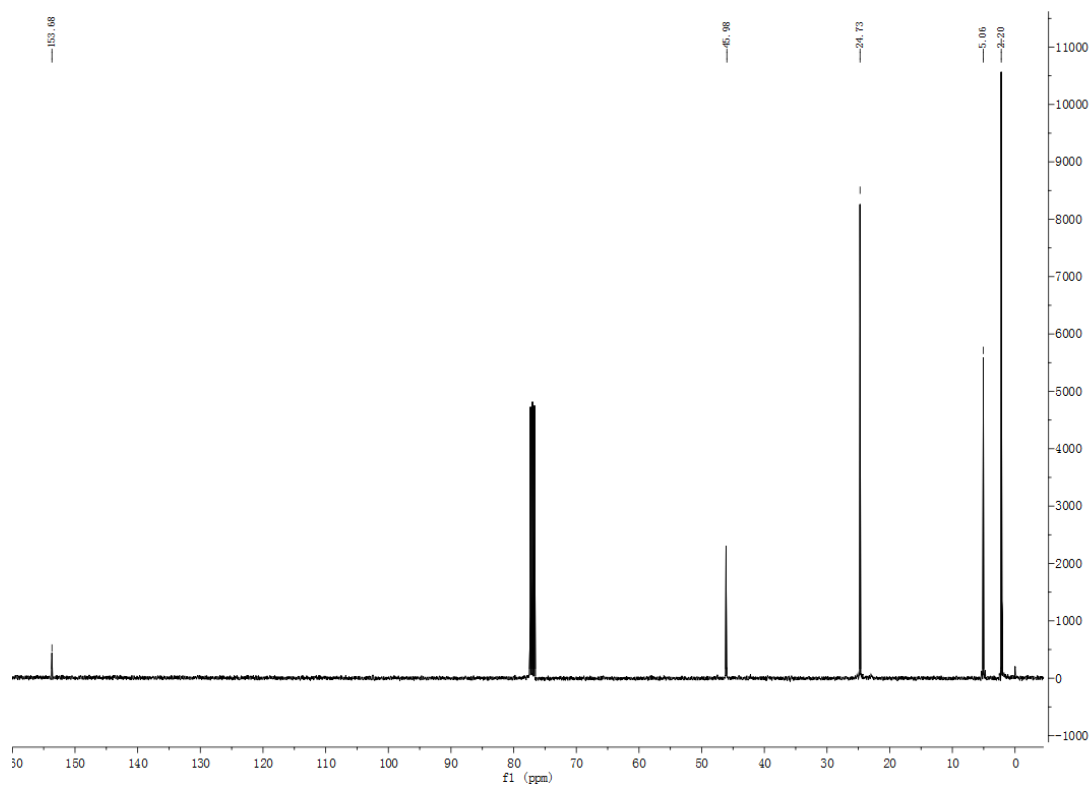
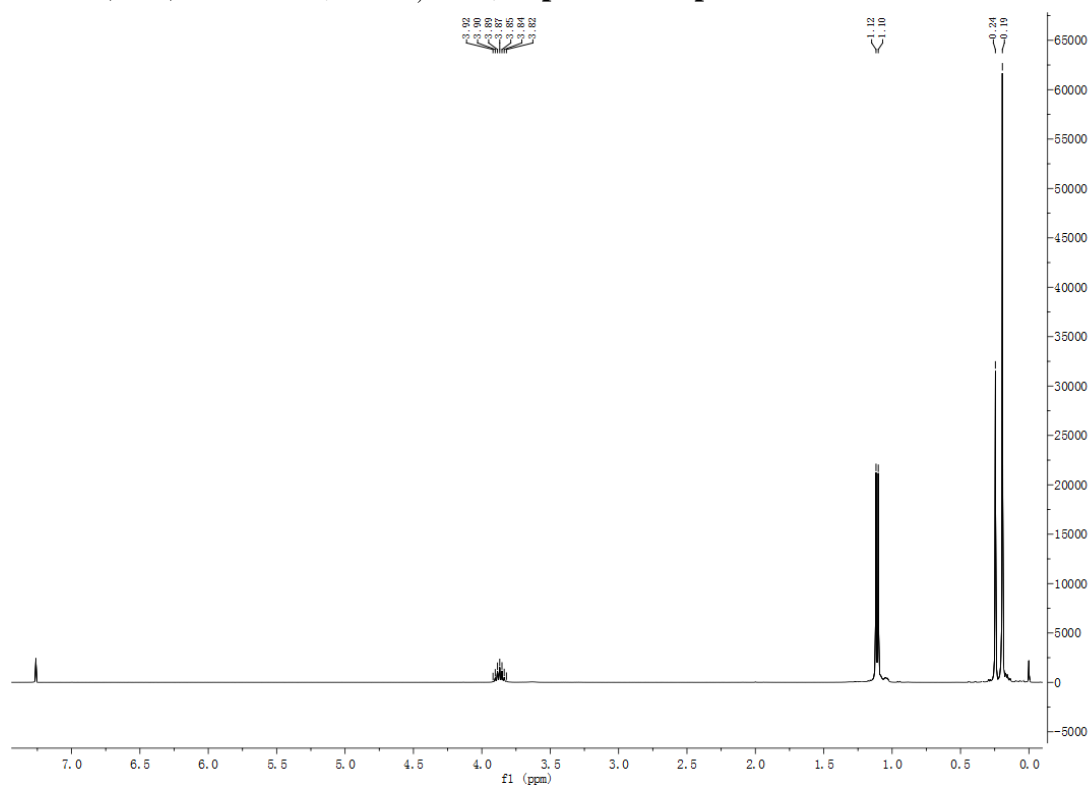
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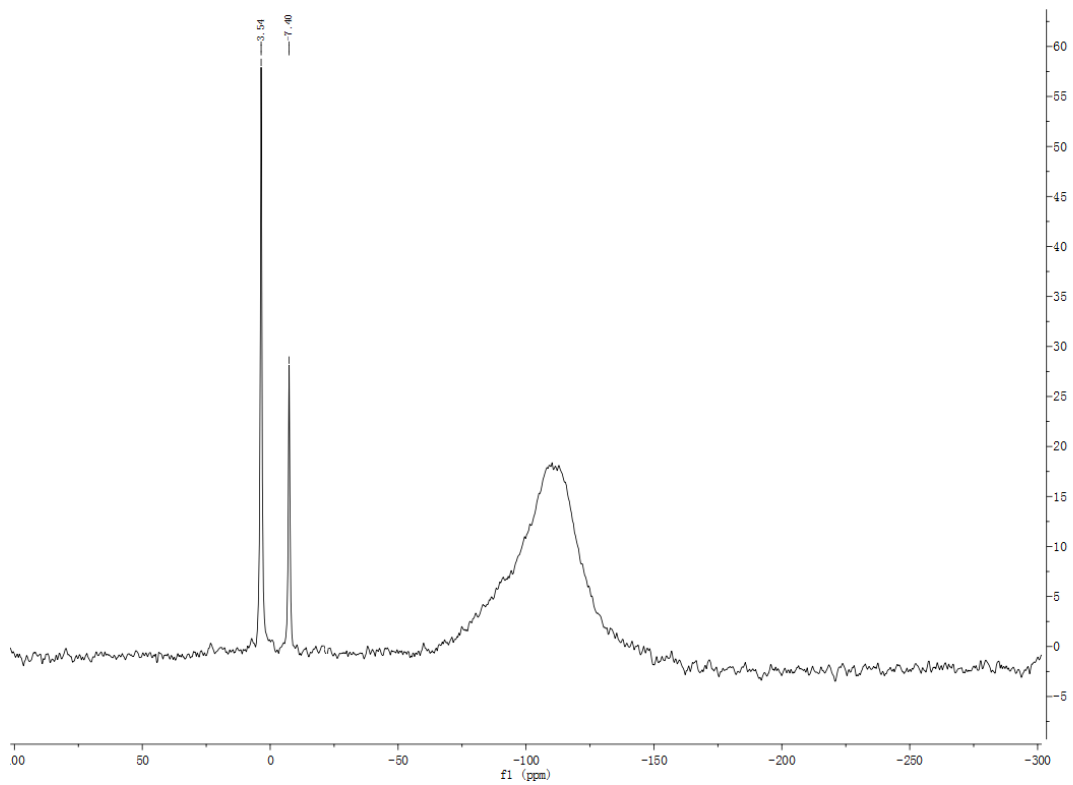
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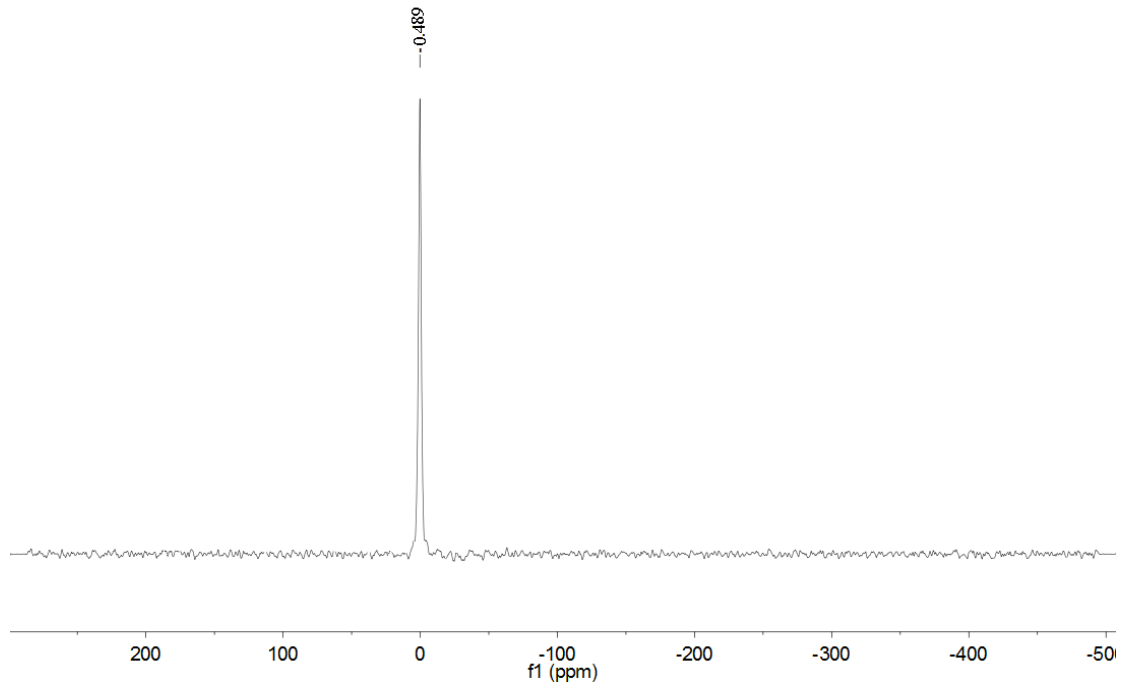
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The ^1H , ^{13}C , ^{29}Si NMR(CDCl_3 , 25°C) copies of compounds 1:

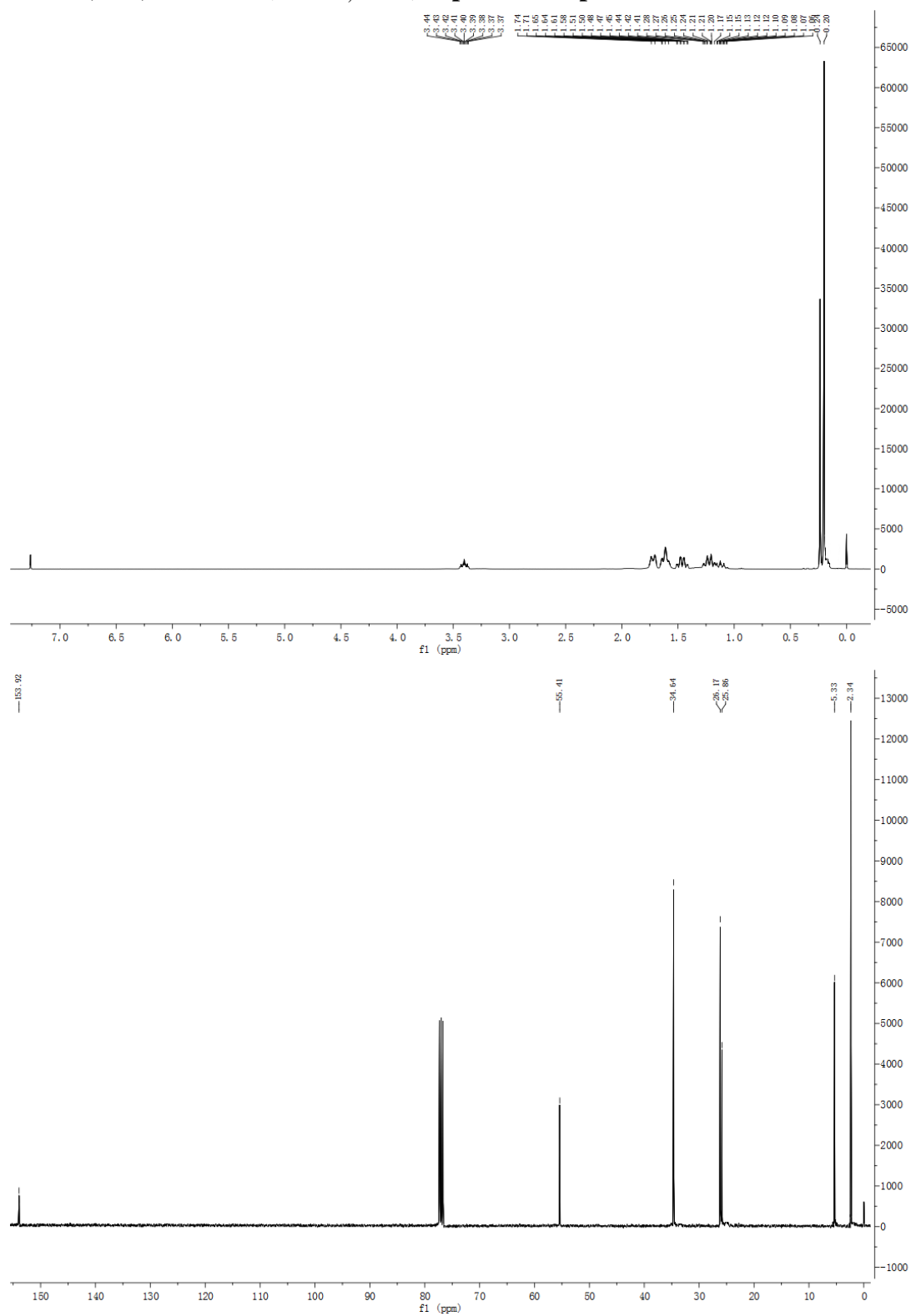


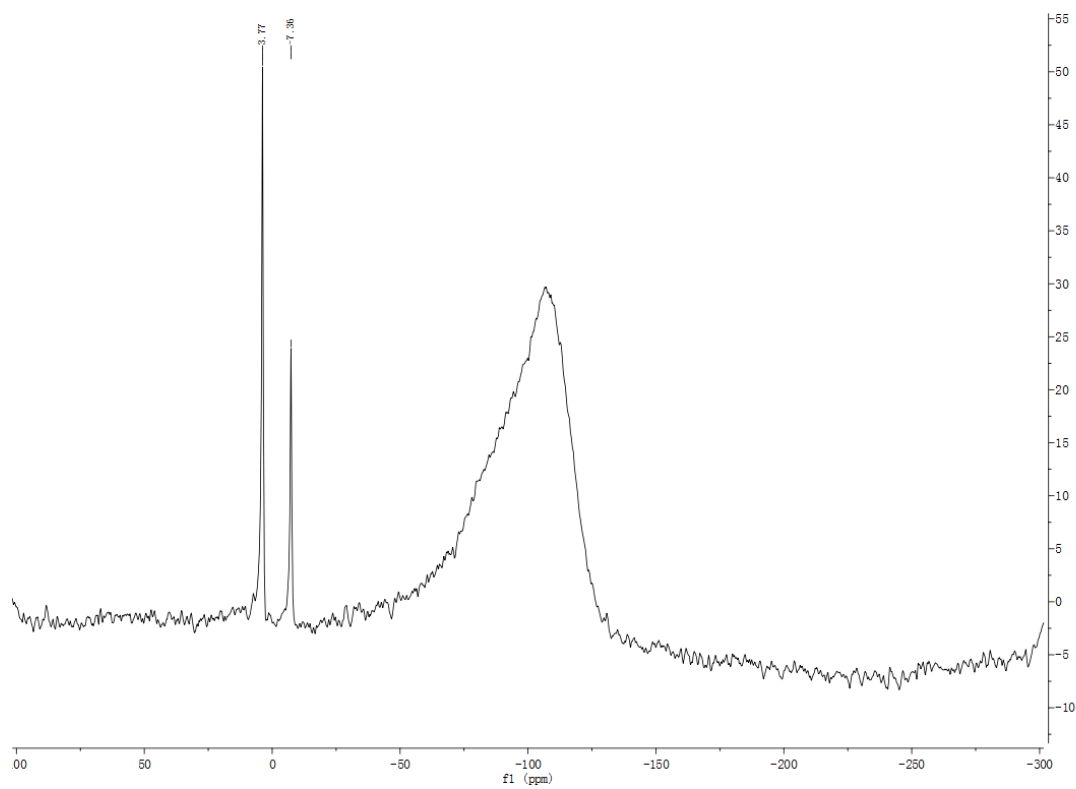


^{29}Si CP/MAS NMR(solid state) :

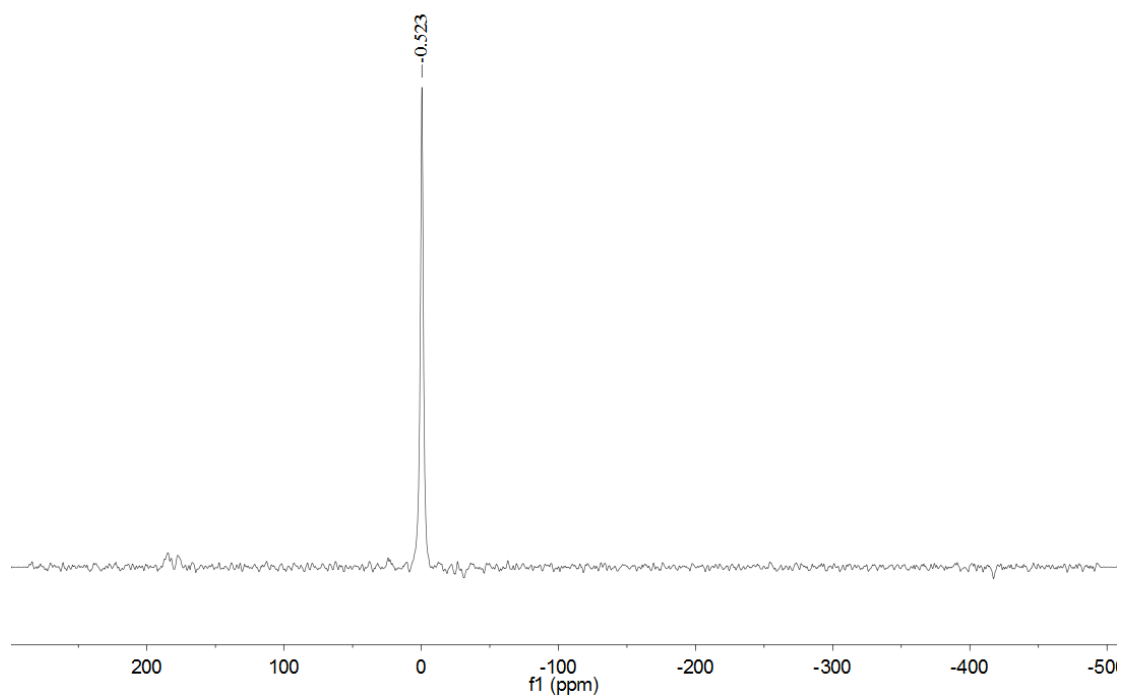


The ^1H , ^{13}C , ^{29}Si NMR(CDCl_3 , 25°C) copies of compounds 2:

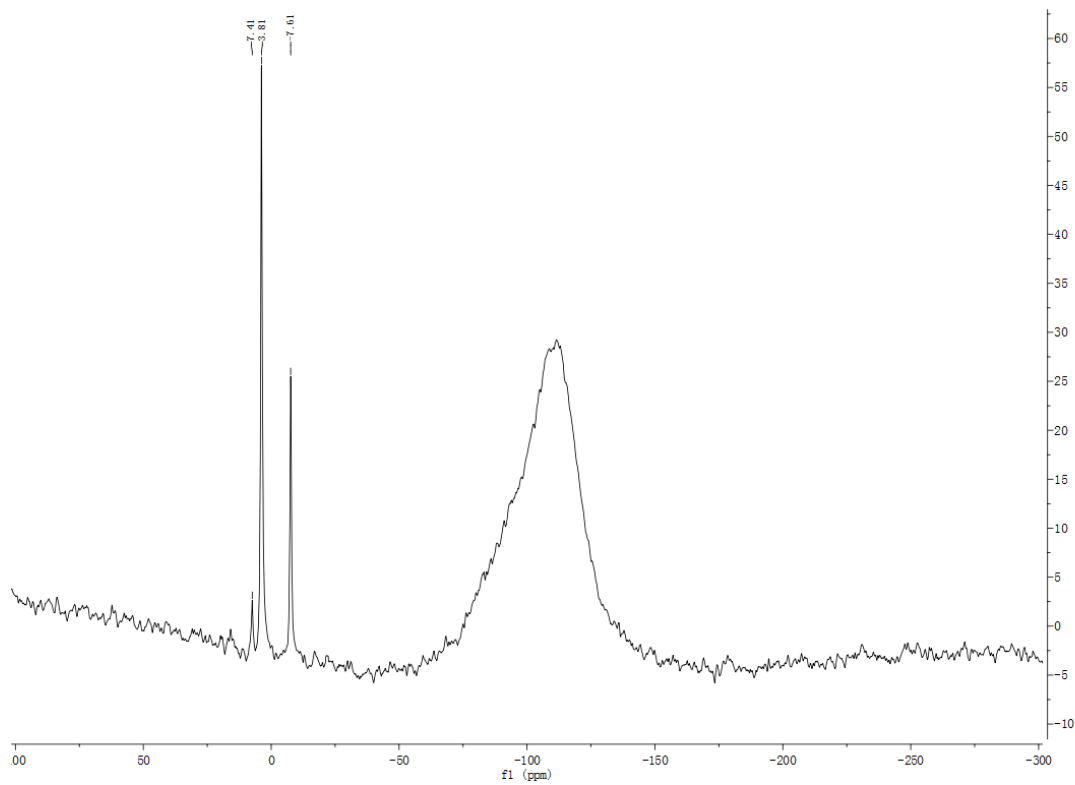




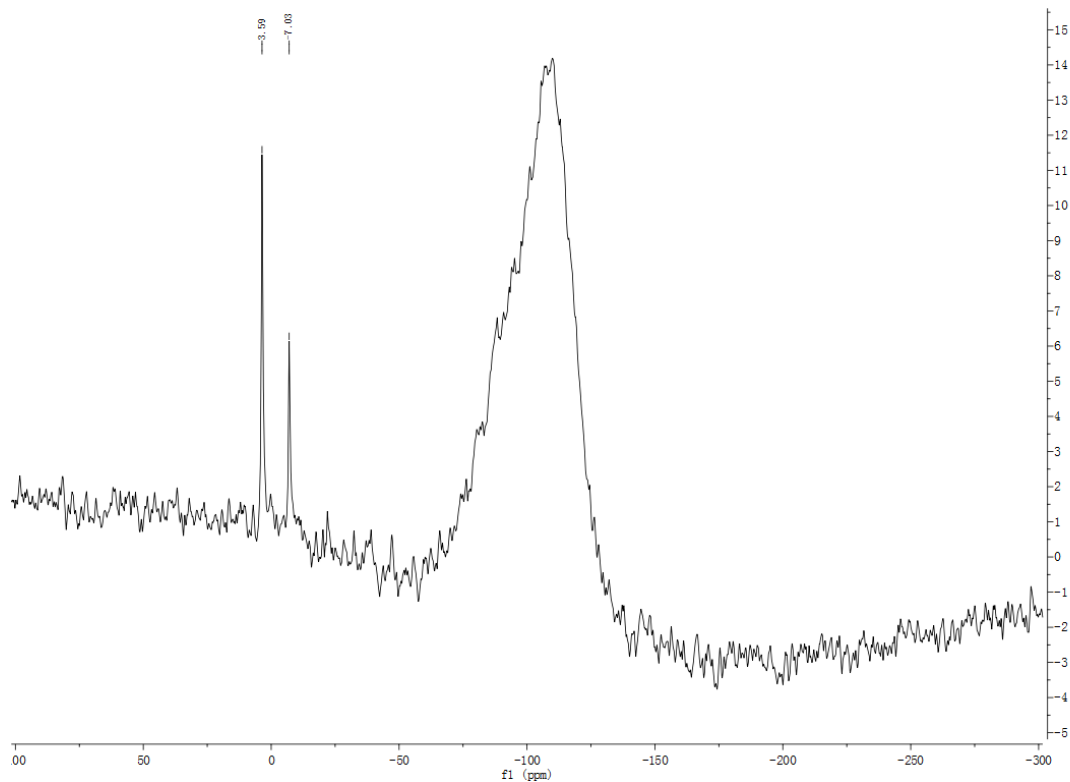
^{29}Si CP/MAS NMR(solid state):



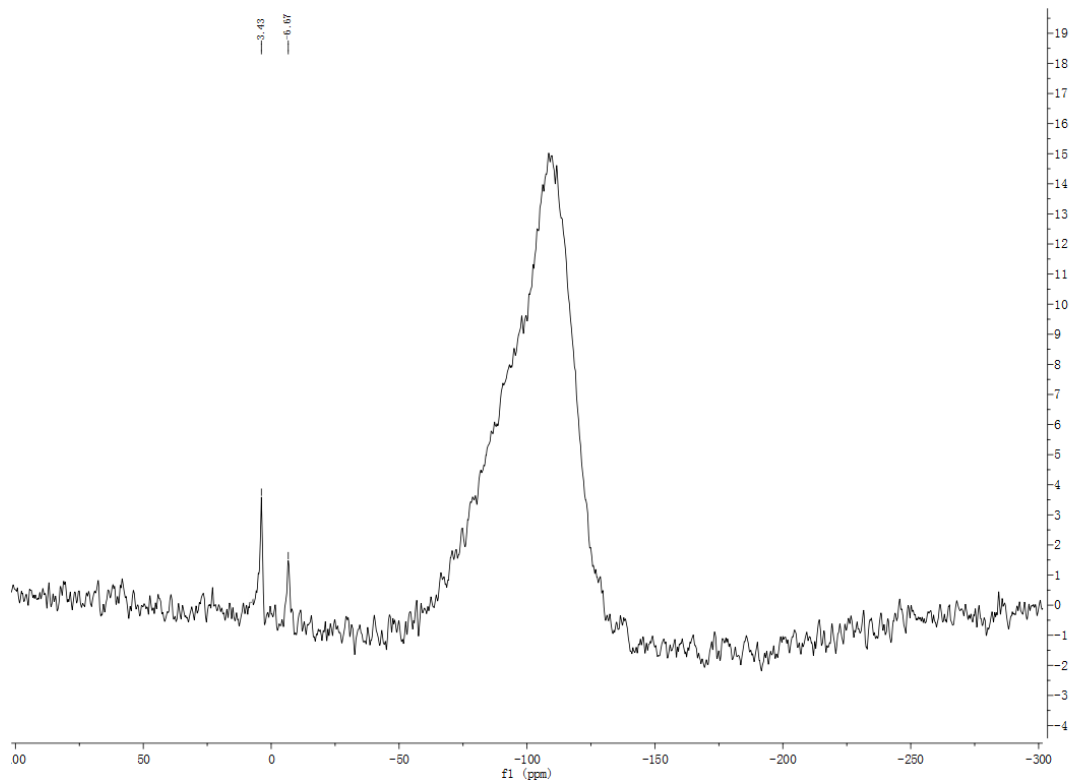
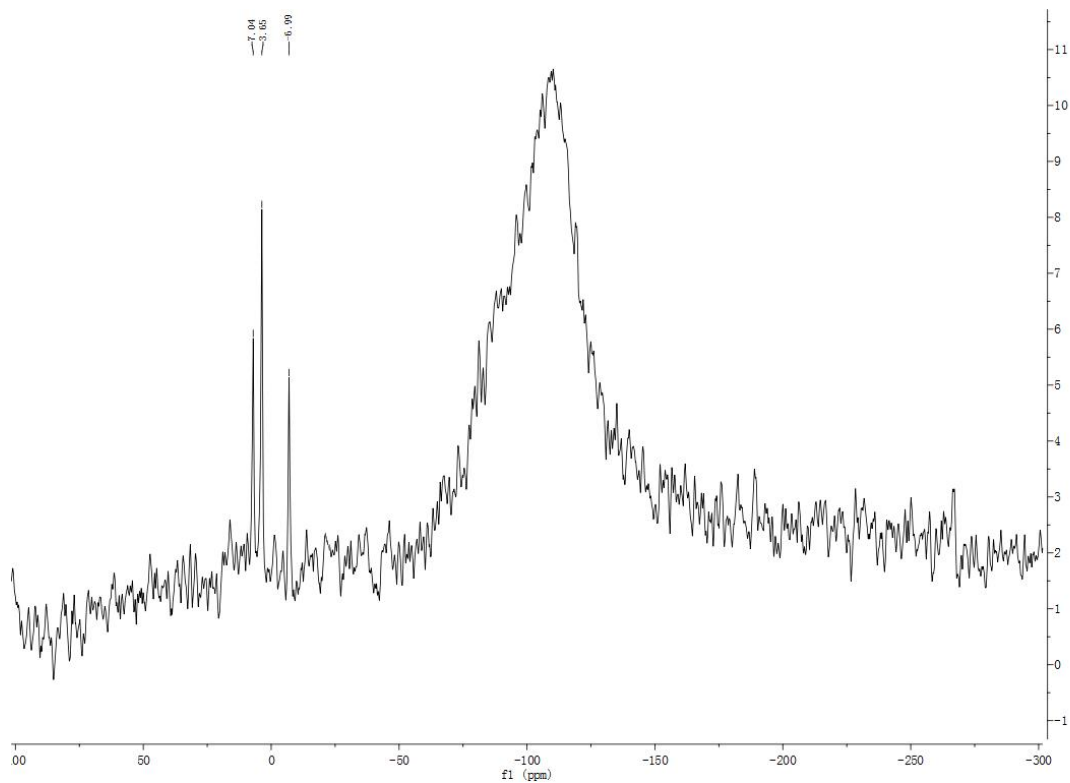
^{29}Si NMR(CD_2Cl_2 , 25°C) copy of compounds 2:



^{29}Si NMR(*d*8-Toluene, 25°C) copy of compounds 2:

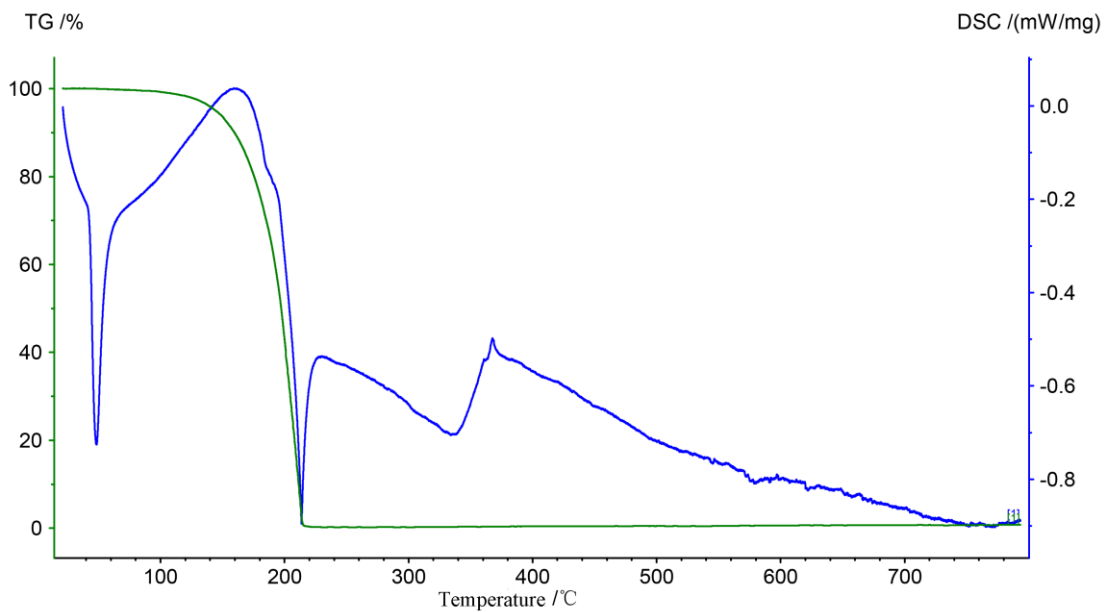


^{29}Si NMR(*d*8-Toluene, 40°C) copy of compounds 2:

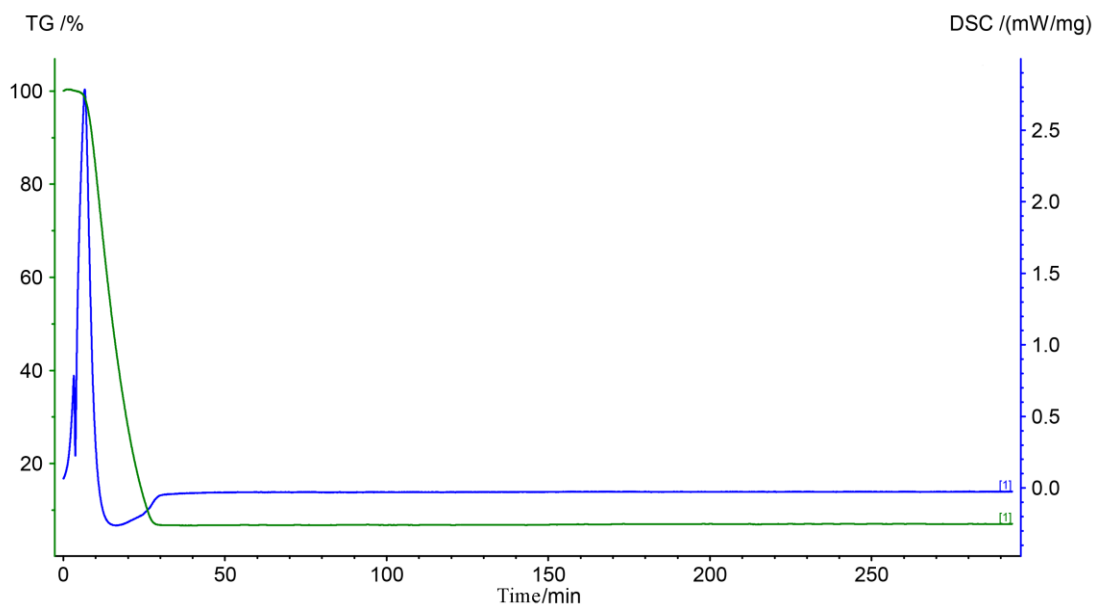


2. STA curves

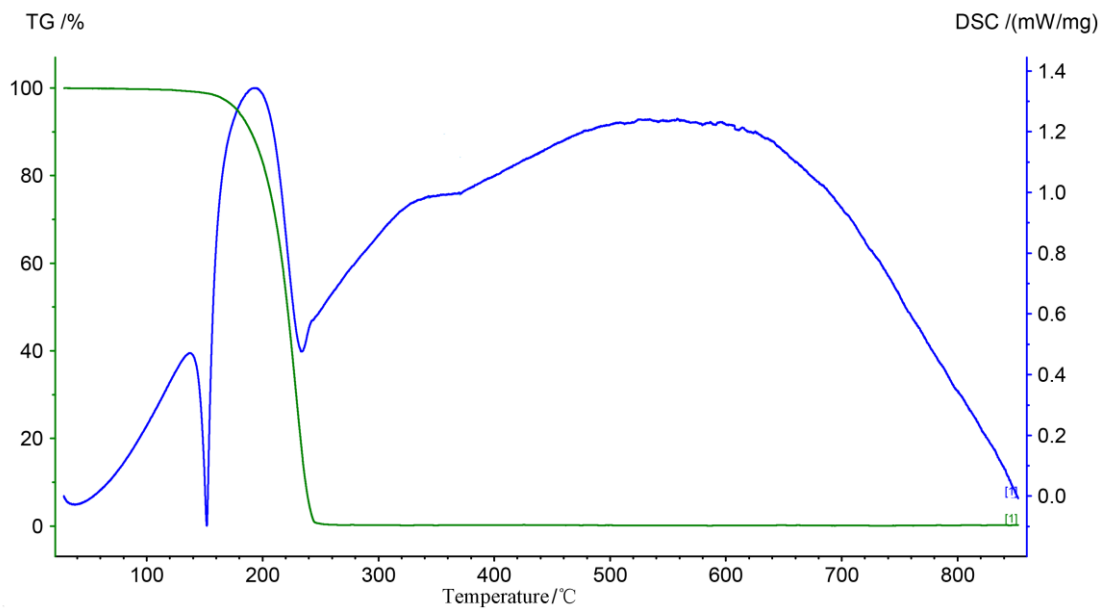
Compound 1:



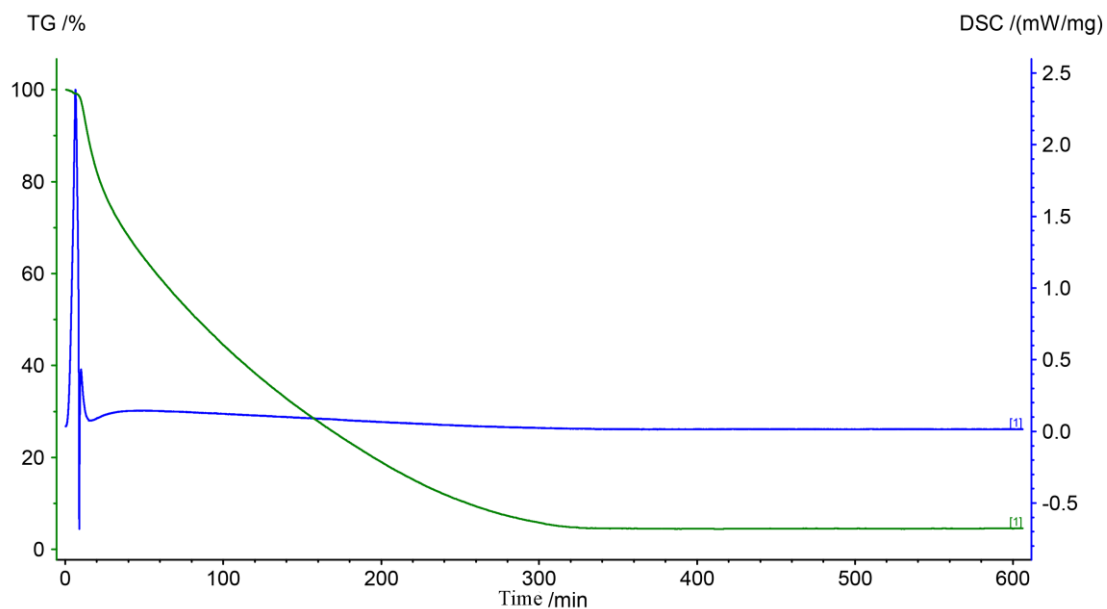
Isothermal TGA of 1 at 150 °C:



Compound 2:

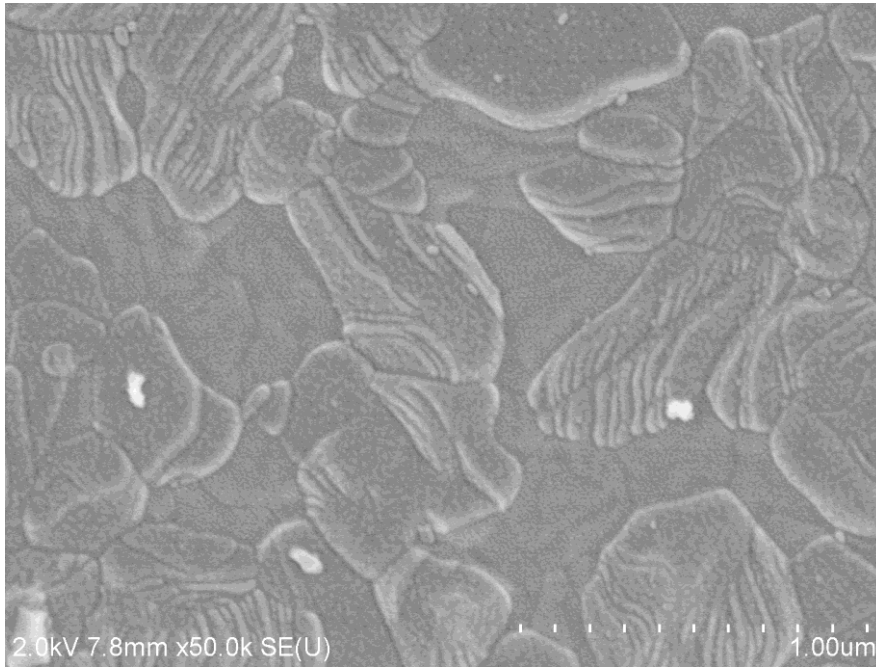


Isothermal TGA of 2 at 150 °C:

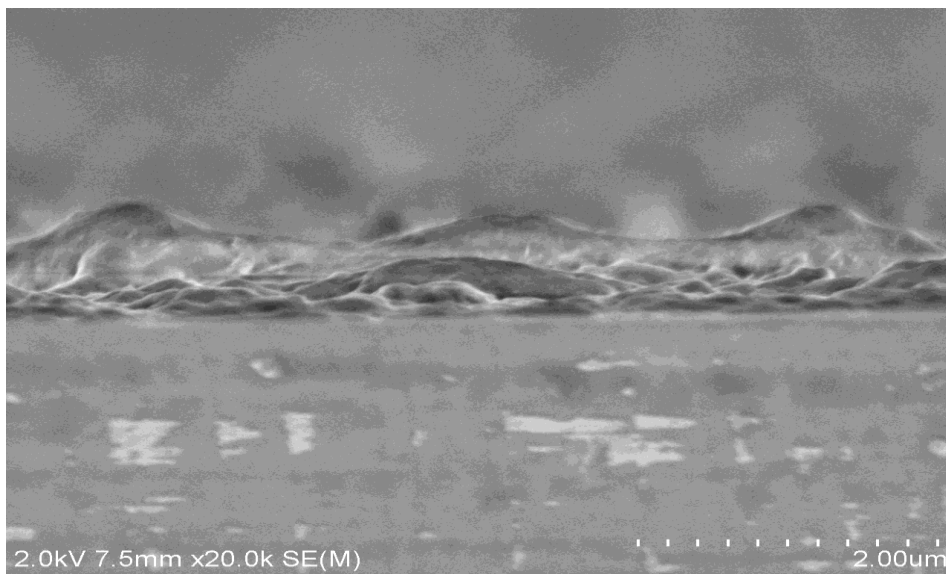


3. SEM images:

Top view of the as-grown film:



cross section SEM image of the film:



4. Deposition furnace:

